

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended): A processing device comprising:

a chamber [[(12)]] defining a processing area;

a mounting table [[(16)]], disposed in the chamber [[(12)]], for mounting thereon an object to be processed; and

a gas supply port [[(19)]] for supplying a gas into the chamber [[(12)]], the gas supply port [[(19)]] being provided at a surface [[(12b)]] of the chamber [[(12)]]; and
a shower head fitted in the gas supply port and having a plurality of gas supply openings at an its surface exposed to an inside of the chamber,

wherein the mounting table [[(16)]] is disposed substantially parallel to the surface [[(12b)]] of the chamber [[(12)]]; and

in a substantially vertical cross section of the chamber [[(12)]] taken along a flow of the gas from the gas supply port [[(19)]] toward the object to be processed, a sidewall [[(12d)]] of the chamber [[(12)]] defining the processing area and abutting on the surface [[(12b)]] of the chamber forms an angle greater than 90° with the surface [[(12b)]] of the chamber and extends close to the mounting table; [[16]] and

the plurality of gas supply openings are provided substantially throughout the exposed surface of the shower head.

Claim 2 (Currently Amended): The processing device of claim 1, wherein the gas supply port [[(19)]] is configured to have a substantially same area as that of the object to be processed.

Claim 3 (Currently Amended): The processing device of claim 1, wherein in a substantially vertical cross section of the mounting table [[(16)]] taken along the flow of the gas from the gas supply port [[(19)]] toward the object to be processed, a mounting surface on which the object to be processed is mounted forms an angle greater than 90° with a side surface of the mounting table [[(16)]] abutting on the mounting surface.

Claim 4 (Currently Amended): The processing device of claim 3, wherein in a substantially vertical cross section of the chamber [[(12)]] and the mounting table [[(16)]] taken along the flow of the gas from the gas supply port [[(19)]] toward the object to be processed, the sidewall [[(12d)]] of the chamber is configured to be substantially parallel to the side surface of the mounting table [[(16)]].

Claim 5 (Currently Amended): The processing device of claim 4, wherein in a substantially vertical cross section of the chamber [[(12)]] and the mounting table [[(16)]] taken along the flow of the gas from the gas supply port [[(19)]] toward the object to be processed, the distance between the sidewall [[(12d)]] of the chamber and the side surface of the mounting table [[(16)]] is set to be less than the distance between the surface [[(12b)]] of the chamber and the object to be processed.

Claim 6 (Currently Amended): A processing device comprising:
a chamber [[(12)]] defining a processing area;
a mounting table [[(16)]], disposed in the chamber [[(12)]], for mounting thereon an object to be processed; and
a gas supply port [[(19)]] for supplying a gas into the chamber [[(12)]], the gas supply port [[(19)]] being provided at a surface [[(12b)]] of the chamber [[(12)]]; .

wherein the mounting table [[(16)]] is disposed substantially parallel to a flow direction of the gas supplied from the gas supply port [[(19)]]; and

in a substantially vertical cross section ~~and/or a substantially horizontal section~~ of the chamber [[(12)]], a sidewall [[(12d)]] of the chamber [[(12)]] defining the processing area and abutting on the surface [[(12b)]] of the chamber forms an angle greater than 90° with the surface [[(12b)]] of the chamber and extends close to the mounting table; [[16]] and

the mounting table has a mounting surface for mounting thereon the object to be processed and a side surface forming an angle greater than 90° with the mounting surface.

Claim 7 (Currently Amended): A processing device comprising:

a chamber [[(12)]] defining a processing area;

a mounting table [[(16)]], disposed in the chamber [[(12)]], for mounting thereon an object to be processed;

a gas supply port [[(19)]] for supplying a gas into the chamber [[(12)]], the gas supply port [[(19)]] being provided at a surface [[(12b, 12a)]] of the chamber [[(12)]]; and

a gas exhaust port [[(13)]] for evacuating the chamber [[(12)]]; and

a shower head fitted in the gas supply port and having a plurality of gas supply openings at its surface exposed to an inside of the chamber,

wherein at least one of sidewalls [[(12d, 12aa)]] of the chamber [[(12)]] defining the processing area and abutting on one surface [[(12b, 12a)]] of the chamber [[(12)]] forms an angle greater than 90° with said one surface [[(12b, 12a)]] of the chamber [[(12)]] and extends close to at least a portion of an outer surface of the object to be processed;

the gas flows a flow passageway whose cross sectional area is gradually increased from the gas supply port [[(19)]] to a proximal end of the object to be processed and is

gradually decreased from a distal end of the object to be processed to the gas exhaust port;

[[(13)]] and

the plurality of gas supply openings are provided substantially throughout the exposed surface of the shower head.

Claims 8-9 (Canceled).

Claim 10 (Currently Amended): A processing device comprising:

a chamber [[(12)]] defining a processing area;

a mounting table [[(16)]], disposed in the chamber [[(12)]], for mounting thereon an object to be processed; and

a gas supply port [[(19)]] for supplying a gas into the chamber [[(12)]], the gas supply port [[(19)]] being provided at a surface [[(12b)]] of the chamber [[(12)]]; and

a shower head fitted in the gas supply port and having a plurality of gas supply openings at an its surface exposed to an inside of the chamber,

wherein in a substantially vertical cross section of the chamber [[(12)]] taken along a flow of the gas from the gas supply port [[(19)]] toward the object to be processed, a sidewall [[(12d)]] of the chamber [[(12)]] defining the processing area and abutting on the surface [[(12b)]] of the chamber extends slant at an angle greater than 90° with respect to the surface [[(12b)]] of the chamber to be close to the mounting table [[16]]; and

a side surface of the mounting table [[16]] is configured to match the slant of the sidewall; [[(12d)]] and

the plurality of gas supply openings are provided substantially throughout the exposed surface of the shower head.

Claim 11 (New): A processing device comprising:

a chamber defining a processing area;

a mounting table, disposed in the chamber, for mounting thereon an object to be processed; and

a gas supply port for supplying a gas into the chamber, the gas supply port being provided at a surface of the chamber;

wherein the mounting table is disposed substantially parallel to a flow direction of the gas supplied from the gas supply port; and

in a substantially horizontal section of the chamber, a sidewall of the chamber defining the processing area and abutting on the surface of the chamber forms an angle greater than 90° with the surface of the chamber and extends close to the mounting table.